

FOCUSED ION BEAM SYSTEM: HITACHI FB-2100

TEM SAMPLE PREPARATION PROCEDURE

This procedure assumes the following:

1. Bulk sample is loaded on the SEM stage.
2. **HV** is on and the tip is conditioned

Procedure

1. Find region of interest:
 - a. Select viewing beam 40-0-30.
 - b. fabrication sub-program.
3. Set **magnification** to 2.0K.
4. Click the square icon at the top-right corner of the left-hand panel. This captures an image on which to overlay the fabrication diagram.
5. Select your deposition and sputtering regions:
 - d. Use **File->Open** to open a pre-

- v. Time/Depth/N: determines how deep the cut is made. If your “material” is available as an option, you can use the “depth” setting. Otherwise you must select a cutting time or number of